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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Makoto KONDO

Application No.: US National Stage of PCT/JP00/01540

Filed: September 26, 2001

Docket No.: 110708

For: EXPOSURE METHOD AND APPARATUS

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 1, between lines 2 and 3, insert a new paragraph as follows:

This application is the national phase under 35 U.S.C. 371 of prior PCT International Application No.PCT/JP00/01540 which has an International filing date of March 14, 2000 which designated the United States of America, the entire contents of which are hereby incorporated by reference.

Page 5, lines 1-18, delete current paragraph and insert therefor:

The present invention provides a first exposure method which stitches and exposes a plurality of patterns on a substrate, thereby exposing a larger pattern than each of the patterns on the substrate, wherein a plurality of patterns are stitched and exposed such that partial regions of the patterns are superposed on each other in a first direction and a second direction which intersect with each other, and, in a region where four patterns are